



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the Application of:

OOHASHI, Takeshi et al.

Group Art Unit: 1711

Serial No.: 09/926,033

Examiner: Not Yet Assigned

Filed: November 7, 2001

P.T.O. Confirmation No.: 3978

For. PHOTSENSITIVE RESIN COMPOSITION, PHOTSENSITIVE ELEMENT  
USING THE SAME, PROCESS FOR PRODUCING RESIST PATTERN AND  
PROCESS FOR PRODUCING PRINTED WIRING BOARD

**SECOND PRELIMINARY AMENDMENT**

Commissioner for Patents  
Washington, D.C. 20231

Date: February 27, 2003

Sir:

Prior to examination of the above-identified application, please note the following  
amendments thereto:

**IN THE SPECIFICATION:**

Please amend the specification as follows:

(Page 30, Table 3):

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ITC 1700 MAIL ROOM

TABLE 3

Materials		Example No.				Comparative Example No.			
		1	2	3	4	1	2	3	4
(A)	a	60	60	-	-	60	60	60	-
	b	-	-	60	60	-	-	-	60
(C)	Nonylphenoxy- octa(ethylenoxy) acrylate	10	10	10	10	-	-	-	-
	Nonylphenoxyethylenoxy acrylate	-	-	-	-	10	-	-	-
	EO, PO-modified urethane dimethacrylate <sup>1</sup>	10	-	10	-	10	10	10	10
	$\beta$ -hydroxypropyl- $\beta'$ - methacryloyloxyethyl o-phthalate	-	-	-	-	-	-	30	-
	2,2-bis[4-(methacryloxy-penta- ethoxy)phenyl]propane	20	30	20	30	20	30	20	30

<sup>1</sup>: A compound of the general formula (IV) wherein R<sup>7</sup> and R<sup>8</sup> each are a methyl group, X<sup>1</sup>  
and X<sup>2</sup> each are an ethylenoxy group, Y<sup>1</sup> and Y<sup>2</sup> each are an isopropyleneoxy group, Z<sup>3</sup> is  
a hexylene group, p and q each are 1, and r and v each are 9.